

Title: METHOD FOR PROVIDING A LIFTOFF PROCESS  
USING A SINGLE LAYER RESIST AND CHEMICAL  
MECHANICAL POLISHING AND SENSOR FORMED THEREWITH  
Applicants: Cyrille, et al.  
Docket: HSJ920030027US1/HITG.025PA  
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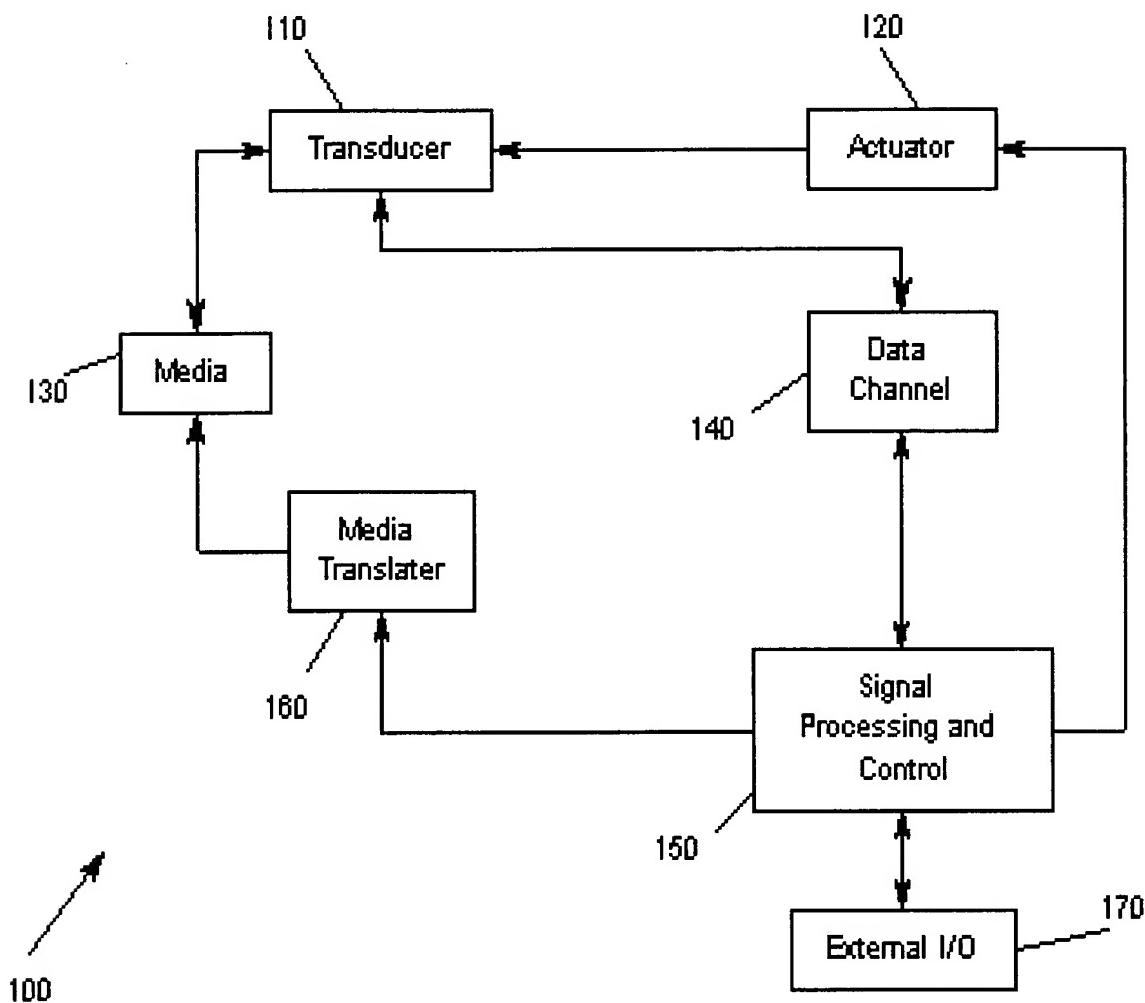


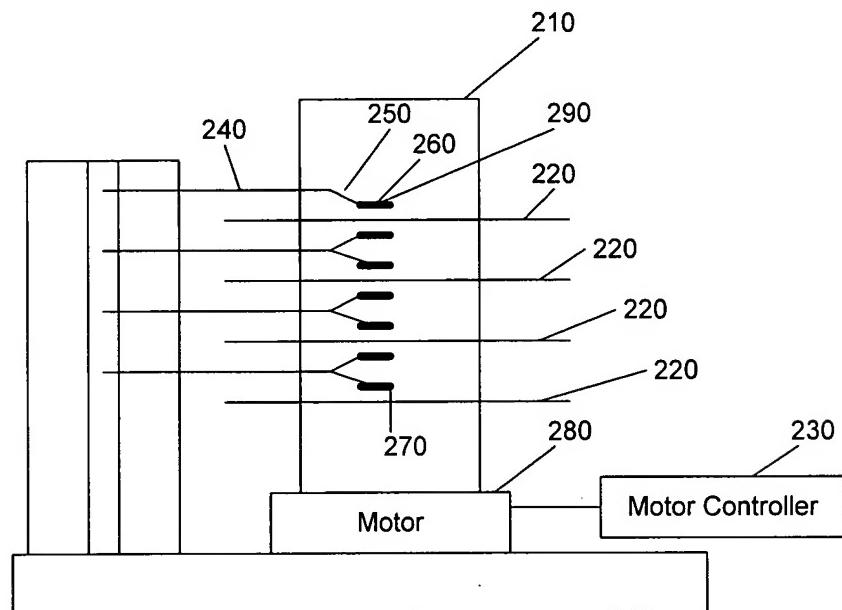
Fig. 1

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***Fig. 2***

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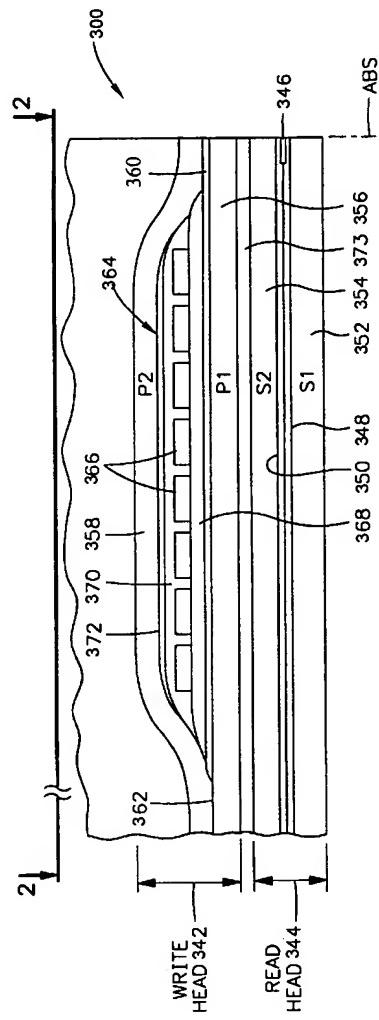


Fig. 3

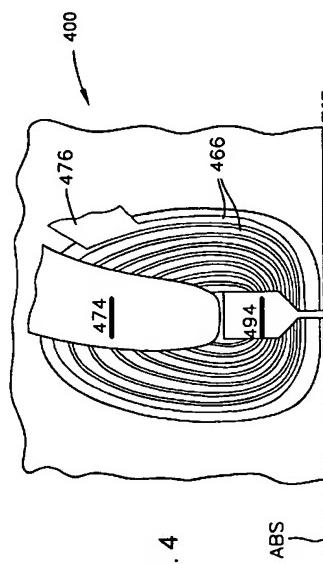


Fig. 4

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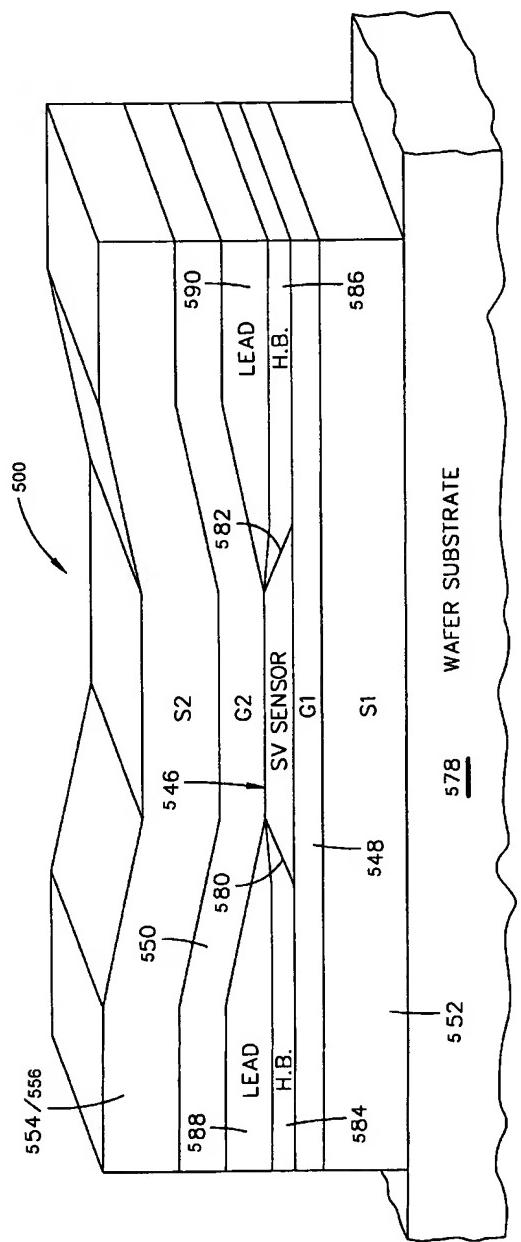


Fig. 5  
(ABS)

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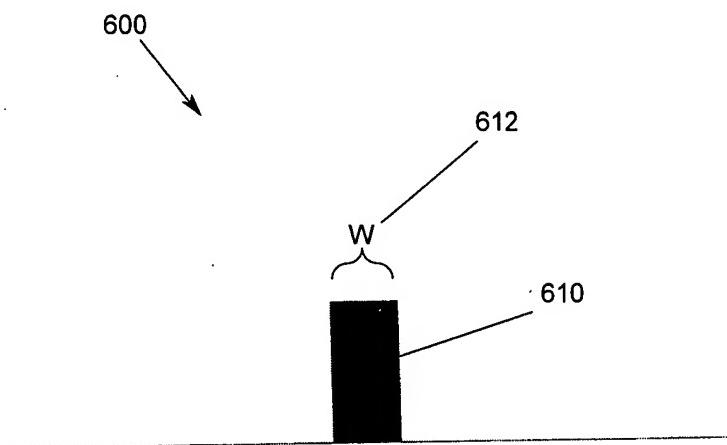


Fig. 6

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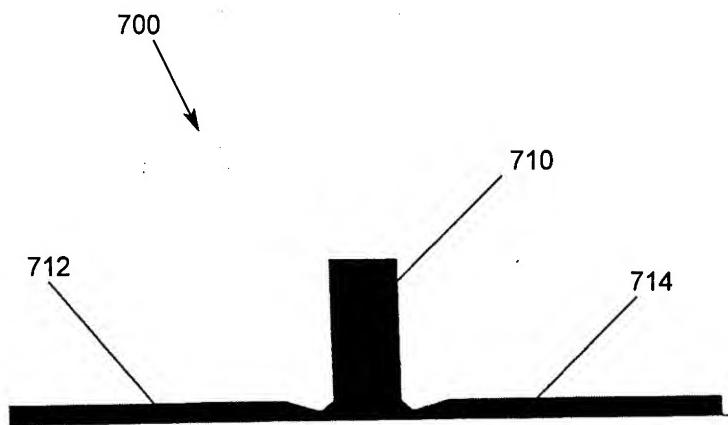


Fig. 7

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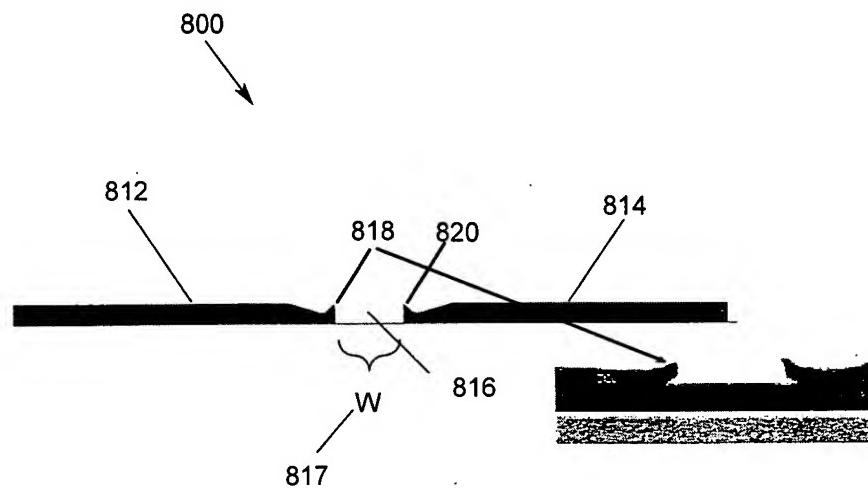


Fig. 8

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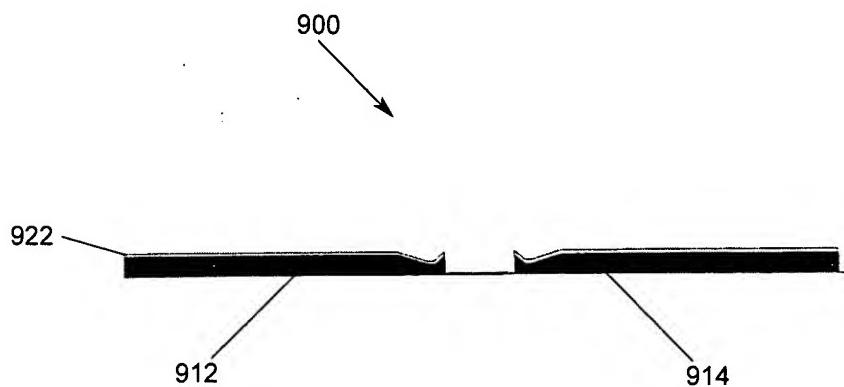


Fig. 9

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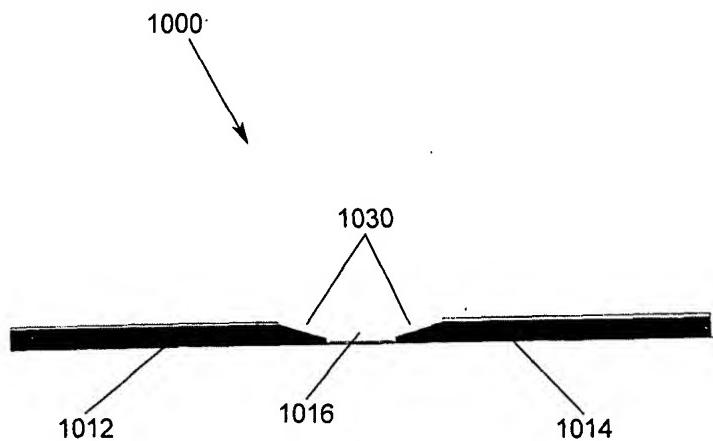


Fig. 10

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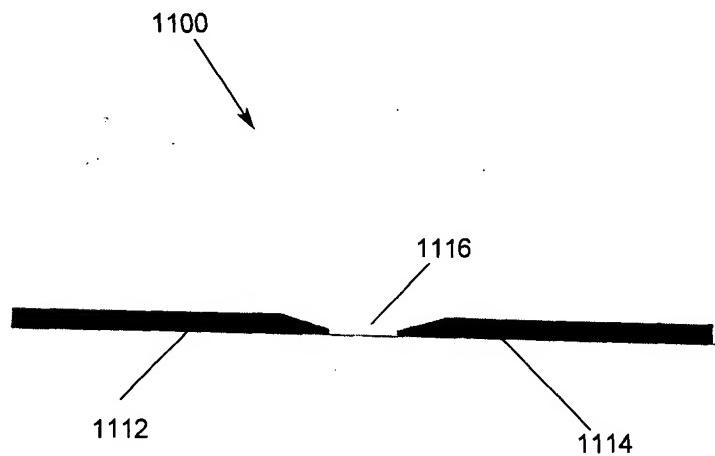


Fig. 11